

What is claimed is:

1. A gas separation apparatus for separating at least one specific gas from a gas to be treated which contains a plurality of specific 5 gases, said apparatus comprising:

 a first separator for separating said gas to be treated into gas groups having different boiling points by distillation separation; and

 a second separator for separating specific gases by performing chromatographic separation on at least one gas group separated by said first separator.

2. A gas separation apparatus according to claim 1, wherein said second separator chromatographically separates a plurality of specific gases having similar boiling points.

3. A gas separation apparatus according to claim 1, wherein said gas to be treated contains PFC gases discharged from a semiconductor manufacturing process as the specific gases and nitrogen as another 20 gas.

4. A gas separation apparatus according to claim 3, wherein said PFC gases contain fluorine compounds having at least one element of C, N, and S as the constituting element.

5. A gas separation apparatus according to claim 3, wherein said PFC gases include at least CF_4 and NF_3 .

6. A gas separation apparatus according to claim 5, wherein said CF_4 and NF_3 are separated into the same gas group at said first separator and are separated from each other at said second separator.

7. A gas separation apparatus according to claim 4, wherein said PFC gases include at least C_2F_6 and CHF_3 .

8. A gas separation apparatus according to claim 7, wherein said C_2F_6 and CHF_3 are separated into the same gas group at said first separator and are separated from each other at said second separator.

9. A gas separation apparatus according to claim 1, wherein
said second separator comprises a plurality of
chromatographic columns;

20 the column into which feed gas flows is sequentially switched among the plurality of chromatographic columns; and the function of each column is sequentially changed.

10. A gas separation method for separating at least one specific
25 gas from a gas to be treated containing a plurality of specific

gases, said method comprising the steps of:

a first separation step for separating said gas to be treated into gas groups having different boiling points by distillation separation; and

5 a second separation step for separating the specific gases by performing chromatographic separation on at least one gas groups that is distillation separated at said first separation step.

10 11. A gas separation method according to claim 10, wherein in said second separation step, a plurality of specific gases having similar boiling points are chromatographically separated.

15 12. A gas separation method according to claim 10, wherein said gas to be treated contains PFC gases discharged from a semiconductor manufacturing process as the specific gases and nitrogen as another gas.

20 13. A gas separation method according to claim 12, wherein said PFC gases include fluorine compounds having at least one element of C, N, and S as the constituting element.

14. A gas separation method according to claim 13, wherein said PFC gases include at least CF_4 and NF_3 .

25 15. A gas separation method according to claim 14, wherein said

CF₄ and NF₃ are separated into the same gas group at said first separation step and are separated from each other at said second separation step.

5 16. A gas separation method according to claim 13, wherein said PFC gases include at least C₂F₆ and CHF₃.

17. A gas separation method according to claim 16, wherein said C₂F₆ and CHF₃ are separated into the same gas group at said first separation step and are separated from each other at said second separation step.

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